

forming a second organic leveling film on the first organic leveling film;
forming a pixel electrode on the second organic leveling film; and
forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,
wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film.

2. (Third Amendment) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first organic leveling film over the gate wiring;
forming a second organic leveling film on the first organic leveling film;
forming a pixel electrode on the second organic leveling film; and
forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,
wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film and
wherein the thickness of the first organic leveling film is 0.1 μm or more and less than 1.5 μm .

3. (Third Amendment) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first organic leveling film over the gate wiring;
forming a second organic leveling film on the first organic leveling film;
forming a pixel electrode on the second organic leveling film; and
forming one of a layer selected from the group consisting of a liquid crystal layer and an

EL layer over the pixel electrode,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film, and

wherein the thickness of the second organic leveling film is from 0.1 μm to 2.9 μm inclusive.

4. (Third Amendment) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;

forming a first organic leveling film over the gate wiring;

forming a second organic leveling film on the first organic leveling film;

forming a pixel electrode on the second organic leveling film; and

forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film, and

wherein the total thickness of the first organic leveling film and the second organic leveling film is from 0.2 μm to 3.0 μm inclusive.

5. (Third Amendment) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;

forming a first organic leveling film over the gate wiring;

forming a second organic leveling film on the first organic leveling film;

forming a pixel electrode on the second organic leveling film; and

forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film, and

wherein the first organic leveling film and the second organic leveling film are insulating films formed by spin coating.

6. (Third Amendment) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first organic leveling film over the gate wiring;
forming a second organic leveling film on the first organic leveling film;
forming a pixel electrode on the second organic leveling film; and
forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film, and

wherein each of the first organic leveling film and the second organic leveling film comprises at least one of a polyimide resin and an acrylic resin.

7. (Third Amendment) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first organic leveling film over the gate wiring;
forming a second organic leveling film on the first organic leveling film;
forming a pixel electrode on the second organic leveling film; and
forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,

wherein the thickness of the first organic leveling film is thinner than that of the second

organic leveling film, and

wherein the first organic leveling film and the second organic leveling film comprise the same material.

8. (Twice Amended) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first organic leveling film comprising resin over the gate wiring;
forming a second organic leveling film comprising resin on the first organic leveling film;
forming a pixel electrode on the second organic leveling film; and
forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,
wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film.

9. (Twice Amended) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming an insulating film comprising an inorganic material over the gate insulating film;
forming a first organic leveling film over the insulating film;
forming a second organic leveling film on the first organic leveling film;
forming a pixel electrode on the second organic leveling film; and
forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,
wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film.

10. (Twice Amended) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
applying a first layer comprising resin by spin coating;
baking the first layer to form a first organic leveling film;
applying a second layer comprising resin by spin coating;
baking the second layer to form a second organic leveling film;
forming a pixel electrode on the second organic leveling film; and
forming one of a layer selected from the group consisting of a liquid crystal layer and an
EL layer over the pixel electrode,
wherein the thickness of the first organic leveling film is thinner than that of the second
organic leveling film.

Cancel Claim 11.

12. A method according to claim 1, wherein the display device is used in one selected
from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 13.

14. A method according to claim 2, wherein the display device is used in one selected
from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 15.

16. A method according to claim 3, wherein the display device is used in one selected
from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 17.

18. A method according to claim 4, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 19.

20. A method according to claim 5, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 21.

22. A method according to claim 6, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 23.

24. A method according to claim 7, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 25.

26. A method according to claim 8, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 27.

28. A method according to claim 9, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

Cancel Claim 29.

30. A method according to claim 10, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

Please add the following new claims:

31. (New) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;

forming a first inorganic film on the gate wiring;

forming a wiring on the first inorganic film;

forming a second inorganic film on the wiring;

forming a first organic leveling film on the second inorganic film;

forming a second organic leveling film on the first organic leveling film;

forming a pixel electrode on the second organic leveling film; and

forming one of a layer selected from the group consisting of a liquid crystal layer and an EL layer over the pixel electrode,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film.

32. (New) A method according to claim 31, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.
